





CR NUMBER:

06PR03921-01

PREVIOUS CR NUMBER: 06PR03921-00

TITLE: DEVELOPMENT OF PROCESS TECHNOLOGIES FOR HIGH-PERFORMANCE MOS-BASED SIC POWER

SWITCHING DEVICES

AWARD NUMBER:

N000140510437

SHORT CONTRACTOR CODE: PRDW

PO PHONE:

POC PHONE:

UIC/CAGE CODE: 6D418

NAVRIS NUMBER:

MODIFICATION NUMBER:

NONPROFIT-EDUC./NOT HISTORICALLY BLACK/OTHER SIZE AND TYPE OF BUSINESS:

COOPER, JAMES A

1012485

PERFORMER:

PURDUE UNIVERSITY

PO NAME: PO CODE: MACK, INGHAM ARTHUR

0312

(703) 696-4825

POINT OF CONTACT:

BROWN, STACY L

GRANTS OFFICER:

FORD, ELIZABETH

CURRENT AWARD START DATE:

01-MAR-05

CURRENT AWARD END DATE:

31-AUG-06

PO REQUESTED START DATE:

17-FEB-06

CR TYPE:

INCREMENTAL FUNDING

INTERNAL COORDINATOR(S)

PHONE

INSTRUMENT TYPE:

BASIS FOR SELECTION:

GRANT BAA

RA

CBD DATE:

24-FEB-06

CURRENT FUNDING:

ACRN APPN

> 0400 1304

255

BCN **RA313**

068342

AAA

TT 2D

PAA 000000

COSTCODE R5720000T972

FY BA

FRC

PE

OBJ PARM

AMOUNT

SA

0

STATUS

FUND SOURCE

OPTION

D 2005

A119 0602716E

SBHD

\$47,843.00

APPROVED

DARPA

NO

FUTURE FRC:

FY FRC

START DATE

AMOUNT

CR STATUS:

APPROVED

\$2,467,843.00

TOTAL VALUE FOR CR:

\$47,843.00

INCREMENTAL VALUE:

\$47,843.00

MODIFICATION NEGOTIATED VALUE:

CUMULATIVE TOTAL AWARD VALUE:

\$47,843.00

of the 3/13/04

Equision Number 307060)

Page 1 of 2

NAVRIS ACQUISITION CR SUMMARY

NOTES:

Short Work Statement

Funds are provided to control and stablize the threshold voltage of IGBTs, grow thick epilayers that can suport 15- 25~kV, and design, fabricate, and characterize SiC IGBTs for the 15 - 25kV regime.

Notes to Acquisition

The design of test chips for both n-channel and p-channel IGBTs has been completed and photomasks have been made. Growth conditions that produce 200 um n-type 4H-SiC blocking layers with good surface morphology and controllable doping in the 1 - 3e14 cm-3 range, as needed for 20 kV n-channel IGBT devices have been established. One of epilayers, with a thickness of 182 um and doping of 1e14 cm-3 was sent to NovaSiC for substrate removal. Experiments have been conducted to assess the efficacy of oxidation or post-oxidation annealing in an alumina environment. additional funds sent by DARPA

FYOS Funds CARROLV / PRODUCT 08-DEC-2005 06PR03921-00

PR Number: 06PR03921-00

Previous PR Number: 304809

Title: Development of Process Technologies for High-Performance

MOS-Based SiC Power Switching Devices

Award Number: N000140510437 Short Contractor Code: prdw Modification Number: P00002 Size and Type of Business: 1p

Nonprofit-Educ./Not Historically

Black/Other

P.I. Name: James Cooper

Performer: PURDUE UNIVERSITY

Point of Contact: Brown Stacy

302 WOOD ST YOUNG HALL

WEST LAFAYETTE, IN 479072108

P.O. Name: Ingham Mack

P.O. Code: 312

P.O. Phone: (703) 696-4825

Phone: (765) 494-1619

Grants Officer:

Current Award Start Date: 01-MAR-05 Current Award End Date: 31-AUG-06 P.O. Requested Start Date: 15-DEC-05 P.O. Requested End Date: 31-AUG-06

PR Type: Incremental Funding

Internal Coordinator(s):

Phone:

Instrument Type: Grant
Basis For Selection: (baa)

CBD Date:

Current Funding:

PA COST

<u>ACRN APPN SBHD OBJ RM BCN SA AAA TT PAA CODE</u> <u>AMOU</u>
AA 9750400 1304 000 RA 31 3 068342 2D 000000R5720000T972 \$820,000.00

FRC: A119 Expiration: 30-SEP-06

Future Funding:

 FY
 FRC
 NEG START DATE
 AMOUNT

 2006 TBD
 01-OCT-05 \$ 47,843.00

PR Status: Committed

Equipment Cost (Current Year): \$ 0.00

CARROLV / PRODUCT 08-DEC-2005 06PR03921-00

Cumulative Total Award Value: \$ 2,467,843.00
Total Value of PR: \$ 820,000.00
Increment Value: \$ 820,000.00
Modification Negotiated Value: \$ 0.00

Short Work Statement

Funds are provided to control and stablize the threshold voltage of IGBTs, grow thick epilayers that can suport 15- 25 kV, and design, fabricate, and characterize SiC IGBTs for the 15 - 25kV regime.

MCCORMD / PRODUCT 03-AUG-2005 05PR07240-01

PR Number: 05PR07240-01

Previous PR Number: 304809

Title: Development of Process Technologies for High-Performance

MOS-Based SiC Power Switching Devices

Award Number: N000140510437

Short Contractor Code: prdw Size and Type of Business: 1p

Modification Number: P00001

Nonprofit-Educ./Not Historically

Black/Other

P.I. Name: James Cooper

Performer: PURDUE UNIVERSITY

302 WOOD ST YOUNG HALL

WEST LAFAYETTE, IN 479072108

P.O. Name: Ingham Mack

P.O. Code: 312

P.O. Phone: (703) 696-4825

Phone: (765) 494-1619

Point of Contact: Brown Stacy Grants Officer:

Current Award Start Date: 01-MAR-05 31-AUG-06 Current Award End Date:

P.O. Requested Start Date: 15-AUG-05

31-AUG-06 P.O. Requested End Date:

PR Type: Incremental Funding

Internal Coordinator(s):

Phone:

Instrument Type: Grant

Basis For Selection: (baa)

CBD Date:

Current Funding:

COST PA CODE PAA TT

AMOU! ACRN APPN SBHD OBJ RM BCN SA AAA AA 9750400 1304 000 RA 31 3 068342 2D 000000R5720000T972 \$80,000.00

FRC: A119 Expiration: 30-SEP-05

Future Funding:

AMOUNT NEG START DATE 01-OCT-05 \$ 867,843.00

PR Status: Committed

0.00 Equipment Cost (Current Year): \$

PR SUMMARY REPORT

MCCORMD / PRODUCT 03-AUG-2005 05PR07240-01

\$ 1,600,000.00 Cumulative Total Award Value: \$ 80,000.00 Total Value of PR: 80,000.00 Increment Value: \$ -671,902.82 Modification Negotiated Value:

Short Work Statement

Funds are provided to control and stablize the threshold voltage of IGBTs, grow thick epilayers that can suport 15- 25 kV, and design, fabricate, and characterize SiC IGBTs for the 15 - 25kV regime.

MCCORMD / PRODUCT 24-FEB-2005 05PR07240-00

PR Number: 05PR07240-00

Previous PR Number:

Title: Wide Bandgap Semiconductor High Power Electronics

Award Number: N000140510437

Short Contractor Code: prdw Size and Type of Business: 1p

Modification Number:

Nonprofit-Educ./Not Historically

Black/Other

P.I. Name: James Cooper

Performer: PURDUE UNIVERSITY

1063 HOVDE HALL

WEST LAFAYETTE, IN 479071063

P.O. Name: Ingham Mack

P.O. Code: 312

P.O. Phone: (703) 696-4825

Phone:

Point of Contact: Grants Officer:

Current Award Start Date: 01-MAR-05 Current Award End Date: 31-AUG-06 P.O. Requested Start Date: 01-MAR-05 P.O. Requested End Date: 31-AUG-06

UG-06 AR-05 UG-06

PR Type: New

Internal Coordinator(s):

Phone:

Instrument Type: Grant
Basis For Selection: (baa)

CBD Date: 08-SEP-04

Current Funding:

PA COST

 ACRN
 APPN
 SBHD
 OBJ
 RM
 BCN
 SA
 AAA
 TT
 PAA
 CODE
 AMOUNTAIN

 AA
 9750400
 1304
 000 RA
 31
 3
 068342
 2D
 000000075720000T972
 \$1,520,000.00

FRC: A119 Expiration: 30-SEP-05

Future Funding:

FY FRC NEG START DATE AMOUNT

PR Status: Approved (Active)

Equipment Cost (Current Year): \$ 0.00

6.2 Juds

MCCORMD / PRODUCT 24-FEB-2005 05PR07240-00

 Cumulative Total Award Value:
 \$ 1,520,000.00

 Total Value of PR:
 \$ 1,520,000.00

 Increment Value:
 \$ 1,520,000.00

 Modification Negotiated Value:
 \$11,503,087.00

Short Work Statement

Funds are provided to control and stablize the threshold voltage of IGBTs, grow thick epilayers that can suport 15- 25 kV, and design, fabricate, and characterize SiC IGBTs for the 15 - 25kV regime.

BPS: Submission, Evaluation, Cost

This proposal was received and evaluated in accordance with The DARPA BAA for WBG High Power Electronics 04-28. Award is recommended based on evaluation of the proposal (provided separately) in accordance with the criteria stated in the announcement/solicitation.

Financial Considerations: Labor -

The proposed quantities and types of labor (including any consultants and labor provided by subgrantee) are reasonable and necessary for accomplishing the research project.

The proposed labor rates are in line with standard academic or industrial practice for research of this type.

Any consulting at a rate in excess of \$500.00 per day is justified in the "Additional Consultant Information" text item.

Other Direct Costs-

Other proposed direct costs (such as supplies, equipment, ADP, travel, etc.) are reasonable and necessary for accomplishing the research project.

I have reviewed and accepted the proposed budget subject to the grant/contracting officer's verification of rates in indirect costs. Where changes to the original budget were necessary I have had the principal investigator submit a revised budget through official university channels and that revised budget is enclosed. The proposal appears to be fair, reasonable, in the interest of the government, and is consistent with other previous and current efforts of this nature.

BPS: Overall Merits

This program will address the needs for implementing a Solid State Power Substation that can be used on navy surface combatants to reduce the size and weight of current systems.

MCCORMD / PRODUCT 24-FEB-2005 05PR07240-00

BPS: ONR Mission

This program will address the need to reduce the size and increase the performance of high power electrical control and conversion systems for naval surface combatants.

BPS: Contractor Qualifications

The members of this team are well qualified to perform the tasks as presented in the proposal. Purdue has experience in SiC devices and applications while other members of the team are known for materials and device characterization as well as process development. All contractors have the facilities to perform the proposed work.

BPS: PI Qualifications

Dr. Cooper has worked in the field of device electronics for 31 years. He is the author/co-author of over 200 technical publications and conference presentations and holds 11 U.S. patents. Dr. Cooper is a recognized leader in the area of power semiconductor devices.

Unclassified PR Number: 05PR07240-00

CLEARANCE MEMORANDUM GRANTS WITH EDUCATIONAL AND NONPROFIT INSTITUTIONS

GRANTEE:

PURDUE UNIVERSITY

SPONSORED PROGRAM SERVICES

302 WOOD ST YOUNG HALL

WEST LAFAYETTE, IN 47907-2040

GRANT NO:

N00014-05-1-0437

AUTHORITY: 10 USC 2358, as amended, and 31 U.S.C. 6304.

1 Selection Procedure: Broad Agency Announcement

This proposal was received in response to the ONRannouncement of research interest published in the COMMERCE BUSINESS DAILY of 08 SEP 04. The Program Officer recommends award based on evaluation of the proposal in accordance with the criteria set forth in the announcement.

2. Proposal Identification.

Title:

Development of Process Technologies for High-Performance MOS-

Based SiC Power Switching Devices

Number:

N/A

Date:

31 AUG 04

As revised:

N/A

3. Principal Investigator: James A. Cooper

4. Document type: Domestic Research Grant

5. Description of Work:

by reference.

The Grantee's proposed work description is incorporated in the Grant

Grant Number: N00014-05-1-0437

6. Analysis of Cost/Price:

A copy of the proposed budget is attached.

- The Program Officer has reviewed the quantities and types of labor, including consultants and subgrantee a. labor, and also the other direct cost items (such as travel, equipment, supplies, materials, ADP, etc.) and has determined them to be appropriate for the proposed research.
- The Specialist has reviewed the budget and determined that the other direct cost items are acceptable. b.

See justification in back-up file.

- The Specialist has reviewed the proposed indirect costs as noted below: C.
 - Fringe Benefit Rate: The proposed rate(s) is/are in accordance with current fixed rates or prospective forward pricing rate(s) and is/are correctly applied to the proper base.
 - Indirect Cost Rate: The Grantee has proposed indirect costs which are in accordance with current policies or as prospectively agreed to until a future negotiation agreement takes effect. The rate(s) is/are correctly applied to the proper base.
- 7. Other Negotiated Terms and Conditions:
 - Negotiated Grant Value: \$ 2,467,843.00 Increment Value: \$ 1,520,000.00

Period covered by increment: 01 MAR 05 to 30 SEP 05

- Period of Performance: 01 MAR 05 to 31 AUG 06
- 8. Certifications:

The appropriate certifications have been submitted by the Grantee and are located in the grant file.

COORDINATED WITH:

Stacy L. Brown

PHONE:

(765) 494-3514

Grant Number: N00014-05-1-0437

9. Reasonableness:

In the opinion of the undersigned, the terms and conditions of this action appear to be fair, reasonable, and

in the best interests of the Government.

Carol A. Porter 14 MAR 05 ONR 251 (703) 696-2587

GRANT NEGOTIATOR DATE CODE TELEPHONE NUMBER

Emme.		· ·		
CONTRACT COMPLETION STATEMENT				
1. FROM: (Award Administration Office)		2a. AWARD NUMBER		
Office of Naval Research, Chicago Regional Office 230 S. Dearborn		N000140510437		
		2b. LAST ADMINISTATION MODIFICATION NUMBER		
Room 380 Chicago, IL 60604-1595		A00002		
Main Office (312) 886-5423Â Â Â Â FAX:(312) 353-2094		2c. LAST AWARDING AGENCY MODIFICATION NUMBER P00003		
3: TO: (Name and Address of Awarding Agency or Payment office, as applicable)		4. NAME OF AWARDEE		
Â OFFICE OF NAVAL RESEARCH 875 NORTH RANDOLPH STREET		Purdue University West Lafayette, IN		
ATTN: BD25 - Mail Room		5. EXCESS FUNDS (ULO)		
ARLINGTONÂ VAÂ 22203-1995		\$0.00		
6a. IF FINAL PAYMENT HAS BEEN MADE,	6b. VOUCHER NUMBER		6c. DATE	
COMPLETE ITMES 6b., and 6c.	018		10/18/2007	
7a. IF FINAL APPROVED INVOICE FORWARDED TO D.O. OF ANOTHER ACTIVITY AND STATUS OF PAYMENT IS UNKNOWN, COMPLETE ITEMS 7b., AND 7c.	7b. INVOICE NUMBER		7c. DATE FORWARDED	
8. REMARKS	<u> </u>		<u> </u>	
Total amount obligated: \$2,461,887.45 \$2,461,887.45 Total amount approved/disbursed: \$2,461,887.45 \$2,461,887.45 Excess funds to deobligate (ULO): \$0.00 \$0.00				
9a. ALL ADMINISTRATION OFFICE ACTIONS REQUIRED HAT THE CASE OF A PRICE REVISION CONTRACT	VE BEEN SATISFACTORILY	COMPLETED. THIS INCLUDES FI	NAL SETTLEMENT IN	
9b. TYPED NAME OF RESPONSIBLE OFFICIAL	9c SIGNATURE	1	9d. DATE	
John Chiappe Administrative Contracting Officer	(b) (6)		07/28/2010	
10a. ALL PURCHASING OFFICE ACTIONS REQUIRED HAVE BEEN FULLY AND SATISFACTORILY ACCOMPLISHED. AWARD FILE OF THIS OFFICE IS HEREBY CLOSED AS OF: ATE SHOWN IN ITEM 9d ABOVE DATE SHOWN IN ITEM 10e BELOW. (Check this box only if final completion of any significant purchasing office action extends more than three months beyond close-out date shown in item 9d, above. In such cases, submit a copy of the completed form upon final accomplishment of all purchasing office actions to the award administration office. (Upon receipt, the award administration office shall extend its contract file close-out date accordingly.)) 10b. REMARKS				
10c. TYPER PAME OF RESPONSIBLE OFFICIAL Contracting Officer DNRUBA FORM 1594, 12/98 V4.30.10	(b) (6)	MURIO.	10e. DATE AUG 07 2010 For Official Use Only	

Advanced Search Information

Search Again Print Record

FOR OFFICIAL USE ONLY

General Information -

Current Registration Status: Active in CCR; Registration valid until 09/27/2006.

DUNS:

072051394

DUNS PLUS4:

CAGE/NCAGE Code:

6D418

Legal Business Name:

PURDUE UNIVERSITY

Doing Business As (DBA):

Division Name: Division Number Company URL:

Physical Street Address 1:401 S GRANT ST

Physical Street Address 2:

Physical City:

WEST LAFAYETTE

Physical State: IN

Physical Zip/Postal Code: 47907-2024

Physical Country:

USA

Mailing Name:

PURDUE UNIVERSITY

Mailing Address:

SPONSORED PROGRAM SERVICES

Mailing Address 2:

302 WOOD ST. (YOUNG HALL)

Mailing City:

WEST LAFAYETTE

Mailing Stato:

IN

Mailing Zip/Postal Code: 47907-2108

Mailing Country:

USA

Business Start Date:

07/02/1862

Corporate Information -

Type of Organization

Corporate Entity, Tax Exempt (State of Incorporation is IN)

Business Types/Grants

A8 - Nonprofit Organization

G6 - 1862 Land Grant College

M8 - Educational Institution

VW - Contracts and Grants

Goods / Services

North American Industry Classification System (NAICS) 611310 COLLEGES, UNIVERSITIES, AND PROFESSIONAL SCHOOLS

> Standard Industrial Classification (SIC) **8221 COLLEGES AND UNIVERSITIES**

> > Product Service Codes (PSC)

Federal Supply Classification (FSC)

- Small Business Types –

This information comes from the Small Business Administration and is not editable by CCR vendors.

Business Types

Expiration Date

North American Industry Classification System (NAICS)

NAICS Code

Description

Small Business

Emerging Small Business

611310

COLLEGES, UNIVERSITIES, AND

No

IN

USA

Ext:

No

PROFESSIONAL SCHOOLS

Points of Contact -

Name:

City:

State:

Country:

Name:

City:

U.S. Phone.

Address Line 1:

Address Line 2:

Zip/Postal Code:

Non-U.S. Phone:

Address Line 1:

Address Line 2:

Government Business POC Primary MIKE LUDWIG

Address Line 1:

PURDUE UNIVERSITY 610 PURDUE MALL

Address Line 2: City:

WEST LAFAYETTE

State: Zip/Postal Code: IN 479072040

Country. U.S. Phone: USA Ext:

Non-U.S. Phone:

7654941063

Past Performance POC Primary

Fax:

Name:

(765) 494-1360

Fax:

(765) 494-1360 Past Performance POC Alternate

479072108

Government Business POC Alternate

REBECCA L. WHITE

WEST LAFAYETTE

(765) 494-1052 Ext:

PURDUE UNIVERSITY

302 WOOD ST. (YOUNG HALL)

Name:

Address Line 1: Address Line 2:

City: State:

Zip/Postal Code: Country:

U.S. Phone:

Non-U.S. Phone:

Fax:

Fax:

State: Zip/Postal Code:

Country:

U.S. Phone: Non-U.S. Phone:

Address Line 1:

Fax:

Name:

City:

Electronic Business POC Primary

Name: MIKE LUDWIG

Address Line 1: PURDUE UNIVERSITY Address Line 2:

Ext:

610 PURDUE MALL **WEST LAFAYETTE**

City: State: IN

Zip/Postal Code: 479072040

Country: U.S. Phone: **USA**

Non-U.S. Phone:

(765) 494-1063 Ext:

(765) 494-1360

Electronic Business POC Alternate

CAROLE PERIGO PURDUE UNIVERSITY

Address Line 2: 610 PURDUE MALL - BURSAR

OFFICE **WEST LAFAYETTE**

State: IN

Zip/Postal Code: 479072040

Country: USA

U.S. Phone:

(765) 494-1024 Ext: Non-U.S. Phone:

Fax: (765) 494-3315

Return to Previous Page Return to Search Page Return to the CCR Home Page Return to the BPN.gov Home Page FOR OFFICIAL USE ONLY

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UNITED STATES PATENT AND TRADEMARK OFFICE

UNDER SECRETARY OF COMMERCE FOR INTELLECTUAL PROPERTY AND DIRECTOR OF THE UNITED STATES PATENT AND TRADEMARK OFFICE

AUGUST 12, 2011

PTAS



103630377A

CAROL PETROSKY
OFFICE OF NAVAL RESEARCH
OFFICE COUNSEL
875 NORTH RANDOLPH STREET
ARLINGTON, VA 22203-1995

UNITED STATES PATENT AND TRADEMARK OFFICE NOTICE OF RECORDATION OF ASSIGNMENT DOCUMENT

THE ENCLOSED DOCUMENT HAS BEEN RECORDED BY THE ASSIGNMENT DIVISION OF THE U.S. PATENT AND TRADEMARK OFFICE. A COMPLETE MICROFILM COPY IS AVAILABLE AT THE ASSIGNMENT SEARCH ROOM ON THE REEL AND FRAME NUMBER REFERENCED BELOW.

PLEASE REVIEW ALL INFORMATION CONTAINED ON THIS NOTICE. THE INFORMATION CONTAINED ON THIS RECORDATION NOTICE REFLECTS THE DATA PRESENT IN THE PATENT AND TRADEMARK ASSIGNMENT SYSTEM. IF YOU SHOULD FIND ANY ERRORS OR HAVE QUESTIONS CONCERNING THIS NOTICE, YOU MAY CONTACT THE EMPLOYEE WHOSE NAME APPEARS ON THIS NOTICE AT 571-272-3350. PLEASE SEND REQUEST FOR CORRECTION TO: U.S. PATENT AND TRADEMARK OFFICE, MAIL STOP: ASSIGNMENT SERVICES BRANCH, P.O. BOX 1450, ALEXANDRIA, VA 22313.

RECORDATION DATE: 08/08/2011

REEL/FRAME: 026740/0763

NUMBER OF PAGES: 2

BRIEF: CONFIRMATORY LICENSE (SEE DOCUMENT FOR DETAILS).

ASSTCNOR:

PURDUE UNIVERSITY

DOC DATE: 07/07/2006

ASSIGNEE:

NAVY, SECRETARY OF THE UNITED STATES OF AMERICA OFFICE OF NAVAL RESEARCH 875 NORTH RANDOLPH STREET ARLINGTON, VIRGINIA 22203-1995

278-12-0001

026740/0763 PAGE 2

APPLICATION NUMBER: 11338007 FILING DATE: 01/23/2006 PATENT NUMBER: 7498633 FILING DATE: 03/03/2009

TITLE: HIGH-VOLTAGE POWER SEMICONDUCTOR DEVICE

TONYA LEE, EXAMINER
ASSIGNMENT SERVICES BRANCH
PUBLIC RECORDS DIVISION

Form PTO-1595 (Rev. 03-09) OMB No. 0651-0027 (exp. 03/31/2009)

08/08/2011



U.S. DEPARTMENT OF COMMERCE United States Patent and Trademark Office

103630377		
To the Director of the U.S. Patent and Trademark Office: Please record the attached documents or the new address(es) below.		
1. Name of conveying party(ies)	2. Name and address of receiving party(ies)	
	Name: NAVY, SECRETARY OF THE UNITED STATES	
PURDUE UNIVERSITY	Internal Address: OF AMERICA	
Additional name(s) of conveying party(ies) attached? Yes X No	20 To 10 To	
3. Nature of conveyance/Execution Date(s):	Street Address: 875 NORTH RANDOLPH STREET	
Execution Date(s) 07/07/2006		
Assignment Merger		
Security Agreement Change of Name	City: ARLINGTON .	
Joint Research Agreement	State: VA	
Government Interest Assignment	-	
Executive Order 9424, Confirmatory License	Country: USA Zip: 22203-1995	
Other	Additional name(s) & address(es) attached? Yes X No	
4. Application or patent number(s):	document is being filed together with a new application.	
A. Patent Application No.(s)	I D. Falcill NO.(3) /\sigma\ A \alpha\	
11/338,007	Received AUG - 8 2011 is	
Additional numbers attr	tached? Yes No	
5. Name and address to whom correspondence	6. Total number of applications and patents	
concerning document should be mailed:	involved: 1	
Name: CAROL PETROSKY	7. Total fee (37 CFR 1.21(h) & 3.41) \$	
Internal Address: OFFICE OF NAVAL RESEARCH		
OFFICE OF COUNSEL	Authorized to be charged to deposit account	
Street Address: 875 NORTH RANDOLPH STREET	Enclosed	
	None required (government interest not affecting title)	
City: ARLINGTON	8. Payment Information	
State: VA Zip: 22203-1995		
Phone Number: 703-696-4008	- 10 A and Street and	
Fax Number: 703-696-6909	Deposit Account Number	
Email Address: CAROL PETROSKY@NAVY MII	Authorized User Name	
9. Signature:		
o. organicano.	07/19/2011 Date	
CAROL RETROSIV	Total number of pages including cover	
CAROL PETROSKY Name of Person Signing	sheet, attachments, and documents:	

Form PTO-1595 (Rev. 03-09) OMB No. 0651-0027 (exp. 03/31/2009)

U.S. DEPARTMENT OF COMMERCE United States Patent and Trademark Office

RECORDATION FORM COVER SHEET PATENTS ONLY			
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1. Name of conveying party(ies)	2. Name and address of receiving party(ies)		
	Name: NAVY, SECRETARY OF THE UNITED STATES		
PURDUE UNIVERSITY	Internal Address: OF AMERICA		
Additional name(s) of conveying party(ies) attached? Yes No			
3. Nature of conveyance/Execution Date(s): Execution Date(s) 07/07/2006	Street Address: 875 NORTH RANDOLPH STREET		
Assignment Merger			
Security Agreement Change of Name	City:arlington		
Joint Research Agreement	State: VA		
Government Interest Assignment			
Executive Order 9424, Confirmatory License	Country: USA Zip: 22203-1995		
Other	Additional name(s) & address(es) attached? Yes X No		
	document is being filed together with a new application.		
A. Patent Application No.(s)	B. Patent No.(s)		
11/338,007			
	tached? Yes No		
5. Name and address to whom correspondence concerning document should be mailed:	6. Total number of applications and patents involved: 1		
Name: CAROL PETROSKY			
Internal Address: OFFICE OF NAVAL RESEARCH	7. Total fee (37 CFR 1.21(h) & 3.41) \$		
OFFICE OF COUNSEL	Authorized to be charged to deposit account		
	Enclosed		
Street Address: 875 NORTH RANDOLPH STREET	None required (government interest not affecting title)		
	8. Payment Information		
City: ARLINGTON	8. Payment information		
State: va Zip: 22203-1995			
Phone Number: 703-696-4008	Descrit Assessed Number		
Fax Number: 703-696-6909	Deposit Account Number		
Email Address: <u>CAROLPETROSKY@NAVY.MIL</u>	Authorized User Name		
9. Signature: (b) (6)	07/19/2011 Date		
CAROL PETROSKY Name of Person Signing	Total number of pages including cover sheet, attachments, and documents:		

License to the United States Government

Sign and Fax this to (301) 480-0272

Invention Title: Optimized Vertical Power DMOSFETS in Silicon Carbide

Inventor(s): Asmita Saha, James A. Cooper

U.S. Filing/Issue Date: 1/23/04

Patent or Application Serial No.: 11/338,007

Grant/Contract Number(s): N00014-02-1-0628

Foreign Applications filed/intended in (countries):

The invention identified above is a Subject Invention under 35 U.S.C. 200, et seq., and the Standard Patent Rights clause at 37 CFR 401.14, FAR 52.227-11 or FAR 52.227-12 (if applicable) which are included among the terms of the above identified grant or contract award from the United State Government. This document is confirmatory of:

- The nonexclusive, nontransferable, irrevocable, paid-up license to practice or have practiced for or on behalf of the United States the invention described in any patent application and in any and all divisions, continuations, and continuations in part, and in any and all patents and re-issues granted thereon throughout the world; and
- 2. All other rights acquired by the Government by reason of the above identified grant/contract award and the laws and regulations that are applicable to the award.

The Government is hereby granted an irrevocable power to inspect and make copies of the above-identified patent application.

Signed this 7th day of July ,20 06.

By Joseph B. Hornett (Name of Grantee/Contractor Official)

Title Senior Vice President and Treasurer

For PURDUE UNIVERSITY (Grantee/Contractor Organization)

At Office of Technology Commercialization Purdue Research Foundation 3000 Kent Avenue WEST

LAFAYETTE, IN 47906 US (Business Address)

ARR1-554641137

REQ708021226

WNR-01-11-054-2-009-01-004

Transfer#: W298-07-0001

Box:1 CC:00

Asset#: AAC1-24157692

Whole Container: N

Created: 8/2/2012

C/F: N00014-99-1-0310 - MIT

Temporary Loan of Records

General Reference

N/A

Standard

Standard (billed)

To: TONYA KILGORE OFFICE OF NAVAL RESEARCH875 NORTH RANDOLPH STREET, CODE 42,

RM 619

ARLINGTON, VA, 22203-1995

P: (703) 696-4623

F: (703) 696-4097



BARNES & THORNBURG LLP

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Customer No.

23643

Group:

2811

Confirmation No.:

4085

Application No.:

11/338,007

Invention:

HIGH-VOLTAGE POWER SEMICONDUCTOR DEVICE

Inventor:

James A. Cooper et al.

Filed:

January 23, 2006

Attorney

Docket:

3220-79132

Examiner:

Unknown

Certificate Under 37 CFR 1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22333-1450

m 4/10/06

(b) (6)

(Printed Name)

PRELIMINARY AMENDMENT UNDER 37 C. F. R. §1.115(a)

Mail Stop Amendment Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Dear Sirs:

Preliminary to the examination of the above-identified national patent application, claiming priority to U.S. Provisional Patent Application No. 60/646,152, Applicants request entry of the amendment to the specification indicated below.

IN THE SPECIFICATION:

Under 37 C.F.R. § 1.121(b) please insert the following after the Title on page 1:

This invention was made with support from DARPA/MTO Grant No. N00014-02-1-0628; the government may have certain rights in this invention.

REMARKS

Applicants do not believe that any fees are due with this Preliminary Amendment; however, the Commissioner is authorized to charge any fees that may be due with this amendment to the deposit account of Barnes & Thornburg account No. (b) (6) with reference to our matter No. 3220-79132.

Respectfully submitted,

BARNES & THORNBURG

(D) (b)

Bradford G. Addison Registration No. 41,486 Attorney for Applicants

BGA/gmk Indianapolis, IN (317) 231-7253



UNITED STATES PATENT AND TRADEMARK OFFICE

UNDER SECRETARY OF COMMERCE FOR INTELLECTUAL PROPERTY AND DIRECTOR OF THE UNITED STATES PATENT AND TRADEMARK OFFICE

JULY 17, 2006

PTAS



CAROL PETROSKY
OFFICE OF NAVAL RESEARCH
OFFICE OF COUNSEL
875 NORTH RANDOLPH STREET
ARLINGTON, VA 22203-1995

UNITED STATES PATENT AND TRADEMARK OFFICE NOTICE OF RECORDATION OF ASSIGNMENT DOCUMENT

THE ENCLOSED DOCUMENT HAS BEEN RECORDED BY THE ASSIGNMENT DIVISION OF THE U.S. PATENT AND TRADEMARK OFFICE. A COMPLETE MICROFILM COPY IS AVAILABLE AT THE ASSIGNMENT SEARCH ROOM ON THE REEL AND FRAME NUMBER REFERENCED BELOW.

PLEASE REVIEW ALL INFORMATION CONTAINED ON THIS NOTICE. THE INFORMATION CONTAINED ON THIS RECORDATION NOTICE REFLECTS THE DATA PRESENT IN THE PATENT AND TRADEMARK ASSIGNMENT SYSTEM. IF YOU SHOULD FIND ANY ERRORS OR HAVE QUESTIONS CONCERNING THIS NOTICE, YOU MAY CONTACT THE EMPLOYEE WHOSE NAME APPEARS ON THIS NOTICE AT 571-272-3350. PLEASE SEND REQUEST FOR CORRECTION TO: U.S. PATENT AND TRADEMARK OFFICE, MAIL STOP: ASSIGNMENT SERVICES BRANCH, P.O. BOX 1450, ALEXANDRIA, VA 22313.

RECORDATION DATE: 05/22/2006

REEL/FRAME: 017944/0901

NUMBER OF PAGES: 2

BRIEF: CONFIRMATORY LICENSE (SEE DOCUMENT FOR DETAILS).

ASSIGNOR;

PURDUE UNIVERSITY

DOC DATE: 03/24/2006

ASSIGNEE:

NAVY, SECRETARY OF THE, UNITED STATES OF AMERICA 875 NORTH RANDOLPH STREET OFFICE OF NAVAL RESEARCH ARLINGTON, VIRGINIA 22203-1995

SERIAL NUMBER: 11338043

FILING DATE: 01/23/2006

PATENT NUMBER. ISSUE DATE:

TITLE: METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE

017944/0901 PAGE 2

ANTIONE ROYALL, EXAMINER ASSIGNMENT SERVICES BRANCH PUBLIC RECORDS DIVISION 06-06-2006



U.S. DEPARTMENT OF COMMERCE United States Patent and Trademark Office

103251548_1			
To the Director of the U.S. Patent and Trademarkloffics. Please record the attached documents or the new address(es) below.			
1. Name of conveying party(ies) PURDUE UNIVERSITY MAY 2 2 2006	2. Name and address of receiving party(ies) Name: NAVY, SECRETARY OF THE, UNITED STATES OF Internal Address: AMERICA		
Additional name(s) of conveying party(ies) attached? No 3. Nature of conveyance/Execution Date(s):	OFFICE OF NAVAL RESEARCH Street Address: 875 NORTH RANDOLPH STREET		
Execution Date(s) 03/24/06 Assignment Merger Security Agreement Change of Name Joint Research Agreement Government Interest Assignment Executive Order 9424, Confirmatory License Other	City:ARLINGTON State:VA Country:USAZip: 22203-1995 Additional name(s) & address(es) attached?YesVNo document is being filed together with a new application. B. Patent No.(s)		
Additional numbers at	ached? ☐ Yes ☑ No		
Name and address to whom correspondence concerning document should be mailed:	6. Total number of applications and patents involved: 1		
Name: CAROL PETROSKY	7. Total fee (37 CFR 1.21(h) & 3.41) \$		
Internal Address: OFFICE OF NAVAL RESEARCH OFFICE OF COUNSEL Street Address: 875 NORTH RANDOLPH STREET	Authorized to be charged by credit card Authorized to be charged to deposit account Enclosed None required (government interest not affecting title)		
City: ARLINGTON	8. Payment Information		
State. VA Zip: 22203-1995	a. Credit Card Last 4 Numbers Expiration Date		
Phone Number: 703-696-4008 Fax Number: 703-696-6909	b. Deposit Account Number CUSTOMER NUMBER Authorized User Name26852		
Email Address: PETROSC@ONR.NAVY.MIL	Additionated Ood Harrie		
9. Signature: (b) (6)	5/17/06 Date		
JAMES BECHTEL Name of Person Signing	Total number of pages including cover sheet, attachments, and documents:		

License to the United States Government

Sign and Fax this to (301) 480-0272
Invention Title: High-Voltage N-Channel Insulated Gate Bipolar Tansistor (IGBT) in Silicon
<u>Carbide</u>
Inventor(s): Xiaokun Wang, James A. Cooper
U.S. Filing/Issue Date: 1/23/ob
Patent or Application Serial No.: 11/338,043
Grant/Contract Number(s): N00014-02-1-0628
Foreign Applications filed/intended in (countries):
The invention identified above is a Subject Invention under 35 U.S.C. 200, et seq., and the Standard Patent Rights clause at 37 CFR 401.14, FAR 52.227-11 or FAR 52.227-12 (if applicable) which are included among the terms of the above identified grant or contract award from the United State Government. This document is confirmatory of:
 The nonexclusive, nontransferable, irrevocable, paid-up license to practice or have practiced for or on behalf of the United States the invention described in any patent application and in any and all divisions, continuations, and continuations in part, and in any and all patents and re-issues granted thereon throughout the world; and All other rights acquired by the Government by reason of the above identified grant/contract award and the laws and regulations that are applicable to the award.
The Government is hereby granted an irrevocable power to inspect and make copies of the above-identified patent application.
Signed this 24th day of March , 20 06 .
By Joseph B. Hornett
Inte Senior Vice President and Treasurer
For PURDUE UNIVERSITY (Grantee/Contractor Organization)
At Office of Technology Commercialization Purdue Research Foundation 3000 Kent Avenue WEST
LAFAYETTE, IN 47906 US (Business Address)

Petrosky, Carol

From: edison@od.nih.gov

Sent: Friday, July 07, 2006 8:47 AM

To: Petrosky, Carol

Subject: iEdison Notification of Patent Confirmatory License Modification

The confirmatory license for the following invention report was modified by Sally Ross on 7/7/06 8:46 AM in the Interagency Edison system.

Invention Report Number: 1481401-05-0026

Patent Docket Number: 64281.00.US

Should you wish to verify the change, you may go to the Interagency Edison system, log in, and view the record for this invention/patent.

Should you have any questions or issues relative to this action, please contact iEdison User Support at edison@od.nih.gov, (301) 435-1986, or toll-free (866) 504-9552.



License to the United States Government

Sign and Fax this to (301) 480-0272			
Invention Title: Optimized Vertical Power DMOSFETS in Silicon Carbide			
Inventor(s): Asmita Saha, James A. Cooper			
U.S. Filing/Issue Date: 1/23/04			
Patent or Application Serial No.: 11/338,007			
Grant/Contract Number(s): N00014-02-1-0628			
Foreign Applications filed/intended in (countries):			
The invention identified above is a Subject Invention under 35 U.S.C. 200, et seq., and the Standard Patent Rights clause at 37 CFR 401.14, FAR 52.227-11 or FAR 52.227-12 (if applicable) which are included among the terms of the above identified grant or contract award from the United State Government. This document is confirmatory of:			
 The nonexclusive, nontransferable, irrevocable, paid-up license to practice or have practiced for or on behalf of the United States the invention described in any patent application and in any and all divisions, continuations, and continuations in part, and in any and all patents and re-issues granted thereon throughout the world; and All other rights acquired by the Government by reason of the above identified grant/contract award and the laws and regulations that are applicable to the award. 			
The Government is hereby granted an irrevocable power to inspect and make copies of the above-identified patent application.			
Signed this 7th day of July 20 06			
By Joseph B. Hornett (Name of Grantee/Contractor Official) (Signature)			
Title Senior Vice President and Treasurer			
For PURDUE UNIVERSITY (Grantee/Contractor Organization)			
At Office of Technology Commercialization Purdue Research Foundation 3000 Kent Avenue WEST			
LAFAYETTE, IN 47906 US (Business Address)			

Form PTO-1595 (Rev. 07/05) OMB No. 0651-0027 (exp. 6/30/2008) U.S. DEPARTMENT OF COMMERCE United States Patent and Trademark Office

RECORDATION FORM COVER SHEET				
PATENTS ONLY				
To the Director of the U.S. Patent and Trademark Office: Please record the attached documents or the new address(es) below.				
1. Name of conveying party(ies)	2. Name and address of receiving party(ies)			
PURDUE UNIVERSITY	Name: NAVY, SECRETARY OF THE, UNITED STATES OF			
PORDOE UNIVERSITY	Internal Address: AMERICA			
Additional name(s) of conveying party(ies) attached? Yes 🗸 No	OFFICE OF NAVAL RESEARCH			
3. Nature of conveyance/Execution Date(s):	Street Address: 875 NORTH RANDOLPH STREET			
Execution Date(s) 03/24/06				
Assignment Merger	City, APLINOTON			
Security Agreement Change of Name	City: ARLINGTON			
Joint Research Agreement	State: VA			
Government Interest Assignment	Country: USA Zip: 22203-1995			
Executive Order 9424, Confirmatory License				
Other	Additional name(s) & address(es) attached? Yes 🗸 No			
	document is being filed together with a new application.			
A. Patent Application No.(s)	B. Patent No.(s)			
11/338,043				
Additional numbers at	tached? Yes No			
5. Name and address to whom correspondence concerning document should be mailed:	6. Total number of applications and patents involved:_1			
Name: CAROL PETROSKY	7. Total fee (37 CFR 1.21(h) & 3.41) \$			
Internal Address: OFFICE OF NAVAL RESEARCH	Authorized to be charged by credit card			
OFFICE OF COUNSEL	Authorized to be charged to deposit account			
Street Address: 875 NORTH HANDOLPH STRELT	Enclosed			
	None required (government interest not affecting title)			
City: ARLINGTON	8. Payment Information			
State: VA Zip: 22203-1995	a. Credit Card Last 4 Numbers Expiration Date			
Phone Number: 703-696-4008	b. Deposit Account Number CUSTOMER NUMBER			
Fax Number: 703-696-6909	,			
Email Address: PETROSC@ONR.NAVY.MIL	Authorized User Name 26852			
9. Signature:	5/17/06			
(0)(0)	Date			
JAMES BECHTEL Name of Person Signing	Total number of pages including cover sheet, attachments, and documents:			

Petrosky, Carol

From:

edison@od.nih.gov

Sent:

Friday, June 16, 2006 10:38 AM

To:

Petrosky, Carol

Subject:

iEdison Notification of Government Support Clause Modification

+ lecense Cliedy recound

The government support clause associated with the following invention report/patent report was modified by Sally Ross on 6/16/06 10:37 AM in the Interagency Edison system.

Invention Report Number: 1481401-05-0025

Patent Docket Number: 64280.00.US

Should you wish to verify the change, you may go to the Interagency Edison system, log in, and view the record for this invention.

Should you have any questions or issues relative to this action, please contact iEdison User Support at edison@od.nih.gov, (301) 435-1986, or toll-free (866) 504-9552.

64280

BARNES & THORNBURG LLP

Bradford G. Addison (317) 231-7253

Email: bradford.addison@btlaw.com

11 South Meridian Street Indianapolis, IN 46204-3535 (317) 236-1313 Fax (317) 231-7433

www.btlaw.com

April 19, 2006

VIA E-MAIL

Ms. Simran Trana
Purdue Research Foundation
Office of Technology Communication
3000 Kent Avenue
West Lafayette, IN 47906

Re:

U.S. Utility Patent Application Serial No. 11/338,043

Title: METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE

Your Reference: 64280.00.US Our Matter: 3220-79131

Dear Simran:

Please find enclosed a copy of a Preliminary Amendment and related document that were filed in the U.S. Patent and Trademark Office on April 10, 2006 in the above-referenced matter. As always, if you should have any questions, please do not hesitate to contact me.

Very truly yours,

BARNES & THORNBURG LLP

Bradford G. Addison

BGA/GMK/kim Enclosures Mailed:

Applicant: Invention:

April 10, 2006
James A. Cooper et al.
METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE
11/338,043
January 23, 2006
3220-79131

Serial No: Filed:

Docket:

X

Preliminary Amendment Under 37 C.F.R. §1.115(a)

The stamp of the Patent Office hereon shows receipt of the indicated papers.

BOAOMK/kim

BARNES & THORNBURG LLP

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Customer No.

23643

Group:

2812

Confirmation No.:

5161

Application No.:

11/338,043

Invention:

METHOD FOR FABRICATING A

SEMICONDUCTOR DEVICE

Inventor:

James A. Cooper et al.

Filed:

January 23, 2006

Attorney

Docket:

3220-79131

Examiner:

Unknown

PRELIMINARY AMENDMENT UNDER 37 C. F. R. §1.115(a)

Mail Stop Amendment Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Dear Sirs:

Preliminary to the examination of the above-identified national patent application, claiming priority to U.S. Provisional Patent Application No. 60/646,151, Applicants request entry of the amendment to the specification indicated below.

Certificate Under 37 CFR 1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

on 41000 (b) (6)

(Printed Name)

IN THE SPECIFICATION:

Under 37 C.F.R. § 1.121(b) please insert the following after the Title on page 1:

This invention was made with support from DARPA/MTO Grant No. N00014-02-1-0628; the government may have certain rights in this invention.

REMARKS

Applicants do not believe that any fees are due with this Preliminary Amendment; however, the Commissioner is authorized to charge any fees that may be due with this amendment to the deposit account of Barnes & Thornburg account No. (b) (6) with reference to our matter No. 3220-79131.

Respectfully submitted,

BARNES & THORNBURG

(b) (6)

Bradford G. Addison Registration No. 41,486 Attorney for Applicants

BGA/gmk Indianapolis, IN (317) 231-7253

From:

edison@od.nih.gov

Sent:

Tuesday, April 25, 2006 1:02 PM

To:

Petrosky, Carol

Subject:

iEdison Notification of Patent Confirmatory License Modification

The confirmatory license for the following invention report was modified by Sally Ross on 4/25/06 1:01 PM in the Interagency Edison system.

Invention Report Number: 1481401-05-0025

Patent Docket Number: 64280.00.US

Should you wish to verify the change, you may go to the Interagency Edison system, log in, and view the record for this invention/patent.

Should you have any questions or issues relative to this action, please contact iEdison User Support at edison@od.nih.gov, (301) 435-1986, or toll-free (866) 504-9552.

64280

License to the United States Government

Sign and Fax this to (301) 480-0272
Invention Title: High-Voltage N-Channel Insulated Gate Bipolar Tansistor (IGBT) in Silicon
<u>Carbide</u>
Inventor(s): Xiaokun Wang, James A. Cooper
U.S. Filing/Issue Date: 1/23/06
Patent or Application Serial No.: 11/338,043
Grant/Contract Number(s): N00014-02-1-0628
Foreign Applications filed/intended in (countries):
The invention identified above is a Subject Invention under 35 U.S.C. 200, et seq., and the Standard Patent Rights clause at 37 CFR 401.14, FAR 52.227-11 or FAR 52.227-12 (if applicable) which are included among the terms of the above identified grant or contract award from the United State Government. This document is confirmatory of:
 The nonexclusive, nontransferable, irrevocable, paid-up license to practice or have practiced for or on behalf of the United States the invention described in any patent application and in any and all divisions, continuations, and continuations in part, and in any and all patents and re-issues granted thereon throughout the world; and All other rights acquired by the Government by reason of the above identified grant/contract award and the laws and regulations that are applicable to the award.
The Government is hereby granted an irrevocable power to inspect and make copies of the above-identified patent application.
Signed this 24th day of March , 20 06.
By Joseph B. Hornett (Name of Grantee/Contractor Official) (Signature)
Title Senior Vice President and Treasurer
For PURDUE UNIVERSITY
(Grantee/Contractor Organization)
At Office of Technology Commercialization Purdue Research Foundation 3000 Kent Avenue WEST

LAFAYETTE, IN 47906 US (Business Address)

From:

edison@od.nih.gov

Sent:

Tuesday, March 21, 2006 10:06 AM

To:

Petrosky, Carol

Subject:

iEdison Not Elect Title Notification

PURDUE UNIVERSITY has chosen not to elect title for the following invention report submitted on 03/21/2006 10:06 am in the Interagency Edison system.

Invention Report Number: 1481401-05-0024

Should you have any questions or issues relative to this action, please contact iEdison User Support at edison@od.nih.gov, (301) 435-1986, or toll-free (866) 504-9552.

02-1-0628

From: '

edison@od.nih.gov

Sent:

Tuesday, October 18, 2005 3:58 PM

To:

Petrosky, Carol

Subject:

iEdison Invention Disclosure Modified Notification

The invention disclosure document associated with the following invention report was modified by Molly Byers on 10/18/05 3:58 PM in the interagency Edison system.

Invention Report Number: 1481401-05-0026

Should you wish to verify the change, you may go to the Interagency Edison system, $\log in_{\mu}$ and view the record for this invention.

From:

edison@od.nih.gov

Sent:

Tuesday, October 18, 2005 3:46 PM

To:

Petrosky, Carol

Subject:

iEdison Invention Disclosure Modified Notification

The invention disclosure document associated with the following invention report was modified by Molly Byers on 10/18/05 3:46 PM in the Interagency Edison system.

Invention Report Number: 1481401-05-0025

Should you wish to verify the change, you may go to the Interagency Edison system, log in, and view the record for this invention.

From:

edison@od.nih.gov

Sent:

Tuesday, October 18, 2005 3:26 PM

To:

Petrosky, Carol

Subject:

iEdison Invention Disclosure Modified Notification

The invention disclosure document associated with the following invention report was modified by Molly Byers on 10/18/05 3:26 PM in the Interagency Edison system.

Invention Report Number: 1481401 05 0024

Should you wish to verify the change, you may go to the Interagency Edison system, $\log in_{i}$ and view the record for this invention.



United States Patent and Trademark Office

UNDER SECRETARY OF COMMERCE FOR INTELLECTUAL PROPERTY AND DIRECTOR OF THE UNITED STATES PATENT AND TRADEMARK OFFICE

SEPTEMBER 08, 2010

PTAS

CAROL PETROSKY.
OFFICE OF NAVAL RESEARCH
OFFICE OF COUNSEL,
875 NORTH RANDOLPH STREET
ARLINGTON, VA 22203-1995

UNITED STATES PATENT AND TRADEMARK OFFICE NOTICE OF RECORDATION OF ASSIGNMENT DOCUMENT

THE ENCLOSED DOCUMENT HAS BEEN RECORDED BY THE ASSIGNMENT DIVISION OF THE U.S: PATENT AND TRADEMARK OFFICE. A COMPLETE MICROFILM COPY IS AVAILABLE AT THE ASSIGNMENT SEARCH ROOM ON THE REEL AND FRAME NUMBER REFERENCED BELOW.

PLEASE REVIEW ALL INFORMATION CONTAINED ON THIS NOTICE. THE INFORMATION CONTAINED ON THIS RECORDATION NOTICE REFLECTS THE DATA PRESENT IN THE PATENT AND TRADEMARK ASSIGNMENT SYSTEM. IF YOU SHOULD FIND ANY ERRORS OR HAVE QUESTIONS CONCERNING THIS NOTICE, YOU MAY CONTACT THE EMPLOYEE WHOSE NAME APPEARS ON THIS NOTICE AT 571-272-3350. PLEASE SEND REQUEST FOR CORRECTION TO: U.S. PATENT AND TRADEMARK OFFICE, MAIL STOP: ASSIGNMENT SERVICES BRANCH, P.O. BOX 1450, ALEXANDRIA, VA 22313.

RECORDATION DATE: 09/02/2010

REEL/FRAME: 024943/0094 NUMBER OF PAGES: 2

BRIEF: CONFIRMATORY LICENSE (SEE DOCUMENT FOR DETAILS).

ASSIGNOR:

PURDUE UNIVERSITY

DOC DATE: 02/22/2010

ASSIGNEE:

NAVY, SECRETRY OF THE UNITED STATES OF AMERICA 875 NORTH RANDOLPH STREET OFFICE OF NAVAL RESEARCH ARLINGTON, VIRGINIA 22203-1995

SERIAL NUMBER: 12429176

FILING DATE: 04/23/2009

PATENT NUMBER:

ISSUE DATE:

TITLE: SIC POWER DMOSFET WITH SELF-ALIGNED SOURCE CONTACTS AND METHOD FOR

MAKING THE SAME

024943/0094 PAGE 2

KIMBERLY WHITE, EXAMINER ASSIGNMENT SERVICES BRANCH PUBLIC RECORDS DIVISION

Form PTO-1595 (Rev. 03-09) OMB No. 0651-0027 (exp. 0

09-02-2010

U.S. DEPARTMENT OF COMMERCE

MB No. 0651-0027 (exp. 03/31/2009)	United States Patent and Tradentalik Office
A SECOND AND A SECOND S	: T
To the Director of the U.S. Patent a. 103606	0.000 occurrents or the new address(es) below.
I. Name of conveying party(ies)	2. Name and address of receiving party(ies)
	Name: NAVY, SECRETRY OF THE UNITED STATES
PURDUE UNIVERSITY	Internal Address: OF AMERICA
Additional name(s) of conveying party(ies) attached? Yes X No	OFFICE OF NAVAL RESEARCH
3. Nature of conveyance/Execution Date(s):	Street Address: 875 NORTH RANDOLPH STREET
Execution Date(s) 02/22/2010	
Assignment Merger	
Security Agreement Change of Name	City: ARLINGTON
Joint Research Agreement	State:VA
Government Interest Assignment	Country: USA Zip: 22203-1995
Executive Order 9424, Confirmatory License	Country. USA 250. 22205 1999
Other	Additional name(s) & address(es) attached? Tyes X No
4. Application or patent number(s):	document is being filed together with copew application.
A. Patent Application No.(s)	document is being filed together with Conservation. B. Patent No.(s) SEP 2 2010 S
	The state of the s
	tached? Yes No 2010's Division
5. Name and address to whom correspondence concerning document should be mailed:	6. Total number of applications and patents involved: 1
Name: CAROL PETROSKY	7. Total fee (37 CFR 1.21(h) & 3.41) \$
Internal Address: OFFICE OF NAVAL RESEARCH	
OFFICE OF COUNSEL	Authorized to be charged to deposit account
Street Address: 875 NORTH RANDOLPH STREET	Enclosed
0.000.700.000	None required (government interest not affecting title)
City: ARLINGTON	8. Payment Information
State: VA Zip: 22203-1995	
Phone Number: 703-696-4008	Deposit Account Number
Fax Number: 703-696-6909	ļ ·
Email Address: CAROL PETROSKY@NAVY.MIL	Authorized User Name
9. Signature: (b) (6)	08/12/2010 Date
Signature	in alluding couler
CAROL PETROSKY	Total number of pages rectionly cover 2 sheet, attachments, and documents:

Documents to be recorded (including cover sheet) should be faxed to (571) 273-8146, or mailed to: Mail Stop Assignment Recordation Services, Director of the USPTO, P.O.Box 1456, Alexandria, V.A. 22313-1450

Name of Person Signing

OMB No. 0651-0027 (exp. 03/31/2009)	United States Patent and Trademark Office
RECORDATION FO	RM COVER SHEET SONLY
To the Director of the U.S. Patent and Trademark Office; Pleas	e record the attached documents or the new address(es) below.
1. Name of conveying party(ies)	2. Name and address of receiving party(ies)
	Name: NAVY, SECRETRY OF THE UNITED STATES
PURDUE UNIVERSITY	Internal Address: OF AMERICA
	OFFICE OF NAVAL RESEARCH
Additional name(s) of conveying party(ies) attached? Yes X No 3. Nature of conveyance/Execution Date(s):	Street Address: _ 875 NORTH RANDOLPH STREET
Execution Date(s) 02/22/2010	Order Address: Order Manager Manager
Assignment Merger	
Security Agreement Change of Name	City: ARLINGTON
Joint Research Agreement	State: VA
Government Interest Assignment	Country: USA Zip: 22203-1995
Executive Order 9424, Confirmatory License	Odditu y. 03A 24p. 22203-1795
Other	Additional name(s) & address(es) attached? Yes X No
1	document is being filed together with a new application.
A. Patent Application No.(s)	B. Patent No.(s)
12/429,176	
Additional numbers at	ached? Yes No
5. Name and address to whom correspondence concerning document should be mailed:	6. Total number of applications and patents involved: 1
Name: CAROL PETROSKY	7. Total fee (37 CFR 1.21(h) & 3 41) \$
Internal Address: OFFICE OF NAVAL RESEARCH	
OFFICE OF COUNSEL	Authorized to be charged to deposit account
Street Address: 875 NORTH RANDOLPH STREET	Enclosed
	None required (government interest not affecting title)
City: _ARLINGTON	8. Payment Information
State: VA Zip: 22203-1995	
Phone Number: 703-696-4008	Descrit Agreement Number
Fax Number: 703-696-6909	Deposit Account Number
Email Address: CAROL PETROSKY@NAVY.MIL	Authorized User Name
9. Signature: (b) (6)	08/12/2010
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Sign and Fax this to (301) 480-0272 Invention Title: SiC Power DMOSFETs with Self-Aligned Source Contacts Inventor(s): Asmita Saha, James A. Cooper, Jr. U.S. Filing/Issue Date: 4/23/2009 Patent or Application Serial No.: 12/429, 176 Grant/Contract Number(s): N00014-05-1-0437 Foreign Applications filed/intended in (countries): The invention identified above is a Subject Invention under 35 U.S.C. 200, et seq., and the Standard Patent Rights clause at 37 CFR 401.14, FAR 52.227-11 or FAR 52.227-12 (if applicable) which are included among the terms of the above identified grant or contract award from the United State Government. This document is confirmatory of: The nonexclusive, nontransferable, irrevocable, paid-up license to practice or have practiced for or on behalf of the United States the invention described in any patent application and in any and all divisions, continuations, and continuations in part, and in any and all patents and re-issues granted thereon throughout the world; and All other rights acquired by the Government by reason of the above identified grant/contract award and the laws and regulations that are applicable to the award. The Government is hereby granted an irrevocable power to inspect and make copies of the above-identified patent application. Signed this day of February 22nd By Joseph B Hornett (Name of Grantee/Contractor Official) Title Senior Vice President and Treasurer FOR PURDUE UNIVERSITY (Grantee/Contractor Organization) At Office of Technology Commercialization Purdue Research Foundation 1281 Win Hentschel



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SERIAL NUMBER: 12429176

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TITLE: SIC POWER DMOSFET WITH SELF-ALIGNED SOURCE CONTACTS AND METHOD FOR

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05-1-0437

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Invention Title: SiC Power DMOSFETs with Self-Aligned Source Contacts
Inventor(s): Asmita Saha, James A. Cooper, Jr.
U.S. Filing/Issue Date:4/23/2009
Patent or Application Serial No.: 12/429,176
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William F. Bahret R. Randall Frisk Robert L. Barlow III

Tel: 317-423-2300 Fax: 317-423-3063

April 27, 2009

Hilton A. Turner, Jr. Innovation Strategy Manager Purdue Research Foundation 1281 Win Hentschel Boulevard West Lafayette, IN 47906-4182

Re:

U.S. Patent Application No. 12/429,176

Filed April 23, 2009

SIC POWER DMOSFET WITH SELF-ALIGNED SOURCE CONTACTS AND METHOD FOR MAKING THE SAME

Inventors: James A. Cooper et al.

Purdue Ref.: 65034.00.US Our Ref.: 13054-285A

Dear Hilton:

We have now completed and filed a regular utility patent application as authorized for the above-identified invention. A copy of the application as filed is enclosed for your records. The accompanying Declaration is not for signature; we will forward a fresh Declaration for signature in the near future.

We anticipate receiving the official filing receipt from the Patent Office within the next 30-60 days, and we will forward it to you upon receipt. In the meantime, please feel free to give me a call if you have any questions.

Note that inventors have a duty to disclose material prior art, including prior products, patents, publications, etc. If you know of any prior art that may be pertinent, please bring it to my attention so that I can include it in an Information Disclosure Statement along with some prior art of which I am already aware.

Our thanks to Jim Cooper for his assistance during the preparation of this application.

Best regards.

Sincerely,

William F. Bahret

WFB/jce Enclosures

cc: James A. Cooper (w/ encls.)

SIC POWER DMOSFET WITH SELF-ALIGNED SOURCE CONTACTS AND METHOD FOR MAKING THE SAME

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CROSS-REFERENCE TO RELATED APPLICATION

This application claims the benefit of U.S. Provisional Patent Application Serial

No. 61/047,274, filed April 23, 2008, which application is hereby incorporated by reference.

GOVERNMENT RIGHTS

This invention was made with government support under Contract/Grant No. W56HZV-06-C-0228 awarded by the U. S. Army TACOM LCMC. The government has certain rights in the invention.

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BACKGROUND OF THE INVENTION

This invention relates generally to semiconductor field effect transistors, and more particularly to field effect transistors having self-aligned source contacts.

The metal oxide semiconductor field effect transistor (MOSFET) is a device used to amplify or switch electronic signals. Power MOSFETs are well known for their ability to carry large currents in the on-state while withstanding large breakdown voltages in the offstate. In such devices, current flow between source and drain regions in a semiconductor substrate is controlled by a voltage applied to a gate electrode that is separated from the semiconductor surface by an insulator, typically silicon dioxide. In an n-type enhancement MOSFET, for example, a positive bias on the gate causes a surface inversion layer – or channel – to form in a p-type region under the gate oxide and thereby creates a conductive path between source and drain. The application of a positive drain voltage then produces current flow between drain and source. Lateral and vertical power MOSFET structures in silicon have been explored over the years, the former type having the drain, gate and source terminals on the same surface of the silicon wafer, the latter type having the source and drain

on opposite surfaces of the wafer. Several different types of vertical power MOSFETs have been proposed, including the double-diffused MOSFET (DMOSFET) and the trench-gate or UMOSFET. These and other power MOSFETs are described in a textbook by B. Jayant Baliga entitled Power Semiconductor Devices, PWS Publishing Co. (1996), the disclosure of, which is hereby incorporated herein by reference.

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Although silicon has been the material of choice for many semiconductor applications, its fundamental electronic structure and characteristics prevent its utilization beyond certain parameters. Thus, interest in power MOSFET devices has turned from silicon to other materials, including silicon carbide. SiC power switching devices have significant advantages over silicon devices, including faster switching speed, lower specific onresistance and thus lower power losses. SiC has a breakdown electric field that is an order of magnitude higher than that of silicon, which allows for a thinner drift region and thus a lower drift region resistance.

In power DMOSFETs, an important performance parameter is the specific on-resistance ($R_{ON,SP}$), which is defined as the product of the resistance when the device is in the "on", or highly conducting, state (low V_{DS}), times the area of the device (units are Ω -cm² or $m\Omega$ -cm²). Thus it is important to minimize both the resistance and the area of the device. For DMOSFETs in the blocking voltage regime of below about 600-1800V, a significant component of the total resistance is the resistance of the source contacts. Larger-area source contacts obviously have lower resistance, but increasing the contact area increases the total area of the device, and hence $R_{ON,SP}$. It is important to find ways to reduce the source contact resistance without increasing the area of the device.

In a conventional DMOSFET, the source contact is defined by photolithography, and the source contact must be separated from the edge of the gate by sufficient distance so that the source contact and gate cannot touch even under worst-case misalignment of the source contact mask. In addition, the actual functional area of the source contact is determined by the overlap of the source contact metal and the N+ implant that forms the source region in the semiconductor. Since the N+ implant is defined by a separate mask, relative misalignment of the source contact mask and the N+ implant mask can reduce the functional area of the source contact, thereby increasing source resistance and degrading performance.

It is desired to produce DMOSFETs and related devices wherein misalignments of source contact and gate are reduced or eliminated.

SUMMARY OF THE INVENTION

The present invention provides high voltage power MOSFETs, with self-aligned source contacts and a method for making the same.

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An intermediate product in the fabrication of a MOSFET, including a silicon carbide wafer having a substrate and a drift layer on said substrate, said drift layer having a plurality of source regions formed adjacent an upper surface thereof; a first oxide layer on said upper surface of said drift layer; a plurality of polysilicon gates above said first oxide layer, said plurality of polysilicon gates including a first gate adjacent a first of said source regions; an oxide layer over said first source region of greater thickness than said first oxide layer; and, an oxide layer over said first gate of substantially greater thickness than said oxide layer over said first source region.

These and other aspects and advantages of the present invention will become more apparent upon reading the following detailed description of preferred embodiments in conjunction with the accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

- FIG. 1 is a side, cross-sectional view of one cell region 10 of a perfectly aligned, conventional DMOSFET 11.
- FIG. 2 is a side, cross-sectional view of the one cell region 10 of FIG. 1 in a worstcase mask misaligned fabrication.
 - FIG. 3 is a side, cross-sectional view of one cell region 20 of a DMOSFET 21 in accordance with the present invention.
- FIG. 4 is a side, cross-sectional view of the cell region 20 of FIG. 3 and shown shifted one half cell width laterally from the view of FIG. 3.
 - FIGS. 5-8 are side, cross-sectional views of one cell region of an intermediate semiconductor product 58 showing various intermediate stages of fabrication of the DMOSFET 21 of Fig. 3.
- FIG. 9 is a layout view of a 10 A DMOSFET formed in accordance with the present invention
 - FIG. 10 is a wafer photograph showing gate and source fingers of the DMOSFET OF FIG. 9 in more detail.

Description of Preferred Embodiments

For the purpose of promoting an understanding of the principles of the invention, reference will now be made to the embodiments illustrated in the drawings and specific language will be used to describe the same. It will nevertheless be understood that no limitation of the scope of the invention is thereby intended, and that alterations and further modifications in the illustrated device and further applications of the principles of the invention as illustrated therein are contemplated as would normally occur to one skilled in the art to which the invention relates. As shown in the Figures, the sizes of some layers or regions are exaggerated to better illustrate the general structures of the present invention, and actual sizes – often with thicknesses of 50 nm – are either specified or are understood by persons of skill in the art to be other than that shown in the Figures.

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It is desired in power DMOSFETs to have a low specific on-resistance ($R_{ON,SP}$), which is defined as the product of the resistance when the device is in the "on", or highly conducting, state (low V_{DS}), times the area of the device (units are Ω -cm² or $m\Omega$ -cm²). It is therefore important to minimize both the resistance and the area of the device. For DMOSFETs with blocking voltage below about 1800V, a significant component of the total resistance is the resistance of the source contacts. While larger-area source contacts obviously have lower resistance, they conversely increase the total area of the device, and hence $R_{ON,SP}$.

Referring to FIG. 1, there is shown one cell region 10 of a perfectly aligned, conventional DMOSFET 11. In DMOSFET 11, the source contact 13 is defined by photolithography, and source contact 13 must be separated from the edge of the gate 14 by sufficient distance **X** so that source contact 13 and gate 14 cannot touch even under worst-case misalignment of the source contact mask. In addition, the actual functional area of the source contact is determined by the overlap **A** of the source contact metal 13 and the N+ implant 15 that forms the source region in the semiconductor. Since the N+ implant 15 is defined by a separate mask, relative misalignment of the source contact mask and the N+ implant mask can reduce the functional area of the source contact, thereby increasing source resistance and degrading performance. A worst-case mask misaligned is shown in FIG. 2 where the Ni metal for the source contact 13' has been misaligned to the right and the P+

B of Ni metal and N+ implant has been reduced almost to zero, resulting in a very large contact resistance for this part of the device. Another drawback of this approach is the alignment tolerance (spacing X) that must be built into the MOSFET design to ensure that the source metal 13 never comes into contact with gate 14 under worst-case misalignment. That is, if the MOSFET design parameters require that source metal 13 never get closer to gate 14 than spacing Y, even under a worst-case mask misalignment (as shown in FIG. 2), then the target mask alignment must be performed with a spacing X. The necessary additional spacing (which is the difference between X and Y) unduly increases the area of the cell, and thus increases R_{ON,SP}. Both these problems – increased contact resistance at reduced area overlap B from mask misalignment and increased cell width to ensure adequate spacing Y - are eliminated in the present invention by negating the opportunity for misalignment of source contact metal and gate.

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Referring to FIG. 3, there is shown one cell region 20 of a double-diffused, power metal-oxide-semiconductor field effect transistor (DMOSFET) 21 in accordance with the present invention. While this and other embodiments presented herein are directed to power DMOSFETs and method for making the same, the present invention is believed to be applicable in varying degrees to other MOSFET designs or similar semiconductor geometry having a source and a gate where it is desirable to place the source and gate as close together as possible and/or to minimize or reduce mask misalignment errors relating to positionment of the gate and source. Such other MOSFETs contemplated by the present invention include, but are not limited to, other vertical MOSFETS, e.g., VMOSFETs and UMOSFETs, as well as lateral DMOSFETs.

DMOSFET 21 includes a substrate 23 and a number of semiconductor layers and implants formed on or in the substrate 23 up through top surface 28, collectively referred to as the substrate body 22. The fabrication of substrate body 22, and variations thereof, can be accomplished in a variety of ways well known in the art and not substantially discussed herein. Substrate 23 and the layers and implants are formed from silicon-carbide and doped with N-type or P-type impurities as shown in FIG. 3 and described herein. In addition to the embodiments described, alternative embodiments are contemplated wherein the compositions

and configurations of the layers and implants, of the impurity concentrations, and of the method and timing of impurity doping and implant creation differs from that described herein and is in any manner suitable for the intended MOSFET task. Substrate 23 is heavily doped with N-type impurities to an "N+" concentration. Formed atop substrate 23 is drift layer 24, which is lightly doped to an "N-" concentration. Atop drift layer 24 is formed a current spreading epilayer (CSL) 25, which is more heavily doped than drift layer 24, but not as heavily doped as substrate 23. Alternative embodiments are contemplated wherein there is no separately formed CSL layer, and the drift layer 24 extends all the way to the top SiC surface 28. Formed in the top of the current spreading layer 25 is a P well 29. The conductivity types may alternatively be the opposite of those described above. That is, both n-channel and p-channel devices are contemplated as part of the present invention.

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It should be understood that the semiconductor device (MOSFET 21) of FIG. 3 may be a single "transistor cell" and that a completely fabricated transistor device may include any number of such semiconductor devices or cells. As such, the present description relating to cell region 20 is with the understanding that the description is applicable to all semiconductor devices that form a larger, fabricated transistor device. For example, the fabricated transistor device may include any number of doped semiconductor wells 29 depending on the number of semiconductor cell regions 20 included therein. In addition, the present embodiment is directed to an interdigitated finger array (as shown in FIG. 10 and described herein), but alternative embodiments are contemplated wherein the number, alignment and interconnection of cell regions 20 may be arranged in a hexagonal cellular array, sometimes referred to as a HEXFET.

Formed within P well 29 are two heavily doped N+ implant source regions 31 and 32 on opposing sides of a heavily doped, central implant P+ base 33, as shown. N+ implant source regions 31 and 32 are heavily doped with N-type impurities to an "N+" concentration, and P+ base 33 is heavily doped with P-type impurities to an "P+" concentration. N+ implants 31 and 32 comprise the two sources of the cell region 10 of MOSFET 21, and P+ base 33 provides ohmic contact to P well 29. The upper surfaces of P+ base 33, of N+ implants 31 and 32, of P well 29 and of CSL epilayer 25 (or of drift layer 24 if there is no

separate CSL epilayer 25) are coplanar and together form the upper surface 28 of substrate body 22.

Referring to FIGS. 3 and 4, FIG. 4 is a view of MOSFET 21 shifted one half cell width laterally from the view of FIG. 3. Formed atop upper substrate surface 28 and centered over the left end 36 of one P well 29 and the right end 37 of an immediately adjacent P well 29 is a polycrystalline silicon (polysilicon) gate 38 that is surrounded along its top, bottom, left and right sides by an insulating layer of silicon dioxide 41. Formed atop P+ base 33 is a Ti/Al contact metal 43, and a Ni contact metal 44 is formed atop Ti/Al contact metal 43. An Ni ohmic contact metal 45 is formed over the entire MOSFET 21, overlapping the polysilicon gate 38, but insulated from it by the thick oxide layer 41 on the top and sides thereof.

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Because gate 38 is completely surrounded by insulating oxide layer 41, its positionment relative to source contacts 31 and 32 is much less critical, and it cannot detrimentally come in contact with any portion of the Ni metal contact 45 due to any mask misalignment during processing. Gate 38 is centered over the JFET region 48 defined in CSL epilayer 25 between the facing ends 36 and 37 of adjacent P wells 29. Ni ohmic contact metal 45 extends over and contacts with the MOSFET 21 sources (N+ implants) 31 and 32, as well as Ti/Al and Ni metals 43 and 44, respectively. Once gate 38 and Ti/Al and Ni metals are formed atop surface 28, the deposition of Ni metal contact 45 over the entire MOSFET 21 (which is later followed by selective etching to expose and access one portion of commonly connected gates 38) makes conformal, direct and self-aligning contact with the Ti/Al and Ni metals 43 and 44 and, most importantly, with N-source implants 31 and 32. A Ti/Au layer 53 is then formed atop Ni metal contact 45, and thus over all of Ni metal contact 45.

Referring to FIG. 5, MOSFET 21 is there shown as an intermediate semiconductor product 58 with all substrate, layers and doping fabricated up through top SiC surface 28 (which together constitute substrate body 22), an oxidation layer 59, a 4000 A thick layer 66 of polysilicon formed across oxidation layer 59, and application of gate mask 62 atop polysilicon layer 66 in preparation for etching away polysilicon layer 59 to create gates 38. The fabrication of intermediate semiconductor product 58, as shown in FIG. 5, can be

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H. DISCI

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Bi	BRIEF DESCRIPTION OF THE INVENTION: Describe the invention in concise, simple terms. What does it do? How does it work? Reduces area of the trousister and eliminates
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V. SPONSO

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VI. INDENTIFICATION OF CONTRIBUTOR(S)

A. PURDUE CONTRIBUTORS:

List below all Purdue persons who are believed to have contributed to the conception or reduction to practice of this invention. Make additional copies as needed.

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B. NON-PURDUE CONTR List any non-Purdue individual practice of this invention.	ABUTORS. Ils who may have worked on eith	er the conception or reduction to
	Non-Purdue Contributor	
First Name: Gamula Company Name: Tutel Company Address \$50 City/State/Zip: Hallaha Phone: 503-613 - 3	Middle Name:	Last Name; Sala RA3-414 Email: asmita, saha @intel.com
(Dr. Solva wor	on employee of	Pundre ECE at the

VII. INVENTION ASSIGNMENT AND CONTRIBUTION CREDIT

I (We) neknowledge and agree that this disclosure is made pursuant to and controlled by the provisions of Purdue University Policy VIII.4.1. To the full extent of my (our) right(s) as inventor(s) of the invention, by signing this document I (we) acknowledge that the invention and all patent ownership and other legal rights relating thereto are unconditionally assigned to Purdue University (and/or its designee Purdue Research Foundation, at the option of Purdue University) for all purposes.

List as inventors those individuals who, individually or jointly, contributed either to the conception or reduction to practice of your invention. In the event that Purdue University (or its designee) files a patent application relating to your disclosure, actual inventorship will be determined as a matter of law by a patent attorney. Do not list any inventor gratuitously. Use your full legal name, including middle name, please sign below and then print: Prof./Dr./Mr./Ms., followed by your full legal name.

I (We) propose to divide any Invention proceeds that are shared with the listed inventor(s) in the proportion(s) specified before each signature below.

Percentage %	Inventor/ Contributor Signature	(Print): Title Full Legal Name	Date
<i>5</i> 0	(b) (6)	PROFESSOR JAMES AUBERT COOPER, JR	1/9/08
50		DR AGMITH SAHA	

If you have any questions, please call 765-494-5784